What is claimed is:

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- 1. An ONO flash memory array for improving a disturbance between adjacent memory cells, comprising:
- a substrate having a first and second buried diffusion regions;
 - a channel between the first and second buried diffusion regions;
 - an ONO layer above the channel for memory storage;
 - a first pocket of a first concentration implanted on one side of the channel close to the first buried diffusion region; and
 - a second pocket of a second concentration implanted on the other side of the channel close to the second buried diffusion region.
 - 2. The memory array of claim 1, wherein the first concentration is higher than the second concentration.
- 20 3. An ONO flash memory array for improving a disturbance between adjacent memory cells, comprising:
 - a substrate having a first and second buried diffusion regions;
 - a channel between the first and second buried diffusion regions;

an ONO layer above the channel for memory storage; and a pocket implanted on one side of the channel close to the first buried diffusion region.